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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/691,080	10/22/2003	Barry E. Burke	MIT8431L	9280

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Theresa A. Lober
T.A. Lober Patent Services
45 Walden Street
Concord, MA 01742

EXAMINER

LUU, CHUONG A

ART UNIT	PAPER NUMBER
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2818

DATE MAILED: 11/02/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No. 10/691,080	Applicant(s) BURKE ET AL.	
	Examiner Chuong A. Luu	Art Unit 2818	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 03 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☐ Responsive to communication(s) filed on ____.
- 2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-20 is/are pending in the application.
- 4a) Of the above claim(s) ____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) ____ is/are allowed.
- 6) ☒ Claim(s) 1-15 and 18-20 is/are rejected.
- 7) ☒ Claim(s) 16 and 17 is/are objected to.
- 8) ☐ Claim(s) ____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on ____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. ____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- * See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|--|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413)
Paper No(s)/Mail Date. ____. |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| 3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date <u>8/12/2005</u> . | 6) <input type="checkbox"/> Other: ____. |

DETAILED ACTION

Response to Arguments

Applicant's arguments with respect to claims 1-20 have been considered but are moot in view of the new ground(s) of rejection.

PRIOR ART REJECTIONS

Statutory Basis

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

The Rejections

Claims 1-6, 12, 14-15 and 18-20 are rejected under 35 U.S.C. 102(b) as being anticipated by Hynecek (U.S.5,972,733).

Hynecek discloses a method making a virtual phase charge coupled device with
(1); (18); (19); (20) forming an electrically conducting charge transfer channel
(24) in a semiconductor substrate (22);
forming an electrically insulating layer (26) on a surface of the substrate (22);
forming a layer of gate electrode material on the insulating layer (26) (see Figure
1);

forming on the gate material layer a first patterned masking layer (70) having apertures that expose regions of the underlying gate material layer that are to form gate electrodes (see Figure 1);

electrically doping the first-pattern-exposed regions of the gate material layer (24) (see column 2, lines 12-40);

forming on the gate material layer a second patterned masking layer (74) having apertures that expose regions of the underlying gate material layer that are to form gaps between gate electrodes (see column 2, lines 41-67);

etching the second-pattern-exposed regions of the gate material layer (see Figure 3);

(2) further comprising removal of the first patterned masking layer after electrically doping first-pattern-exposed regions of the gate material layer (see Figure 1);

(3) further comprising removal of the second patterned masking layer after etching second-pattern-exposed regions of the gate material layer (see Figure 1);

(4) wherein the first-pattern-exposed regions of the gate material layer are electrically doped before the second-pattern-exposed regions of the gate material layer are etched (see Figure 1);

(5) wherein electrically doping first-pattern-exposed regions of the gate material layer comprises ion implantation of a selected electrical dopant into the first-pattern-exposed regions of the gate material layer (see column 2, lines 12-40);

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(6) wherein etching the second-pattern-exposed regions of the gate material layer comprises plasma etching the second-pattern-exposed regions of the gate material layer (see Figure 3);

(12) wherein forming an electrically insulating layer on a surface of the substrate comprises forming a layer of oxide on the substrate surface (see Figures and 3);

(14) wherein forming a layer of gate electrode material on the insulating layer comprises depositing a layer of polysilicon on the insulating layer (see Figures and 3);

(15) wherein forming a first patterned masking layer and forming a second patterned masking layer each comprise forming a layer of photoresist that is photolithographically patterned (see Figures and 3).

PRIOR ART REJECTIONS

Statutory Basis

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

The Rejections

Claims 7-11 and 13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hynecek (U.S.5,972,733) in view of Rhodes (U.S.4,742,016) and further in view of Erhardt (U.S. 5,114,833).

Hynecek teaches everything above except for heat treating the electrically doped gate electrodes. However, Rhodes discloses a semiconductor device with **(7)** further comprising heat treating the electrically-doped and etched gate electrode material layer to diffuse the electrical dopant through the gate material layer thickness (see column 5, lines 4-27); **(8)** wherein heat treating the electrically-doped and etched gate electrode material layer comprises annealing the gate material layer (see column 5, lines 4-27); **(9)** wherein heat treating the electrically-doped and etched gate electrode material layer comprises oxidation of the gate material layer (see column 5, lines 4-27); **(10)** wherein forming a first patterned masking layer and forming a second patterned masking layer each comprise forming a masking layer having a pattern the apertures of which are characterized by an extent accounting for lateral dopant diffusion during the heat treatment (see column 4, lines 20-57 and column 5, lines 4-27).

Hynecek and Rhodes disclose the above outlined features except for wherein forming an electrically conducting charge transfer channel in a semiconductor substrate comprises ion implantation of a selected electrical dopant into a silicon substrate, the selected electrical dopant being of a conductivity type opposite that of the silicon substrate; wherein forming a layer of gate electrode material on the insulating layer comprises depositing a layer of amorphous silicon on the insulating layer. However, Erhardt discloses a charge-coupled-device with **(11)** wherein forming an electrically

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conducting charge transfer channel in a semiconductor substrate comprises ion implantation of a selected electrical dopant into a silicon substrate, the selected electrical dopant being of a conductivity type opposite that of the silicon substrate (see column 2, lines 36-58. Figures 5-9); **(13)** wherein forming a layer of gate electrode material on the insulating layer comprises depositing a layer of amorphous silicon on the insulating layer; It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the teachings of Hyncek and Rhodes (accordance with the teaching of Erhardt), since it has been held to be within the general skill of a worker in the art to select a known material on the basis of its suitability for the intended use as a matter of obvious design choice. In re Leshin, 125 USPQ 416.

Allowable Subject Matter

Claims 16-17 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chuong A. Luu whose telephone number is (571) 272-1902. The examiner can normally be reached on M-F (6:15-2:45).

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on (571) 272-1787. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



Chuong Anh Luu
Patent Examiner
October 27, 2005